

**AGNOSTIC VALIDATION TEST BENCH FOR EFUSE  
CONNECTIVITY VERIFICATION**

**By**

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## **List of Abbreviations**

<b>Abbreviation</b>	<b>Meaning</b>
API	Application Program Interface
BIOS	Basic Input Output System
CPU	Central Processing Unit
CRP	Challenge Response Pair
DFD	Design for Debug
DFT	Design for Test
DMI	Direct Media Interface
DUT	Device Under Test
ECAM	Enhanced Configuration Access Mechanism
eFUSE	Electronic Fuse / Electric Fuse
EUT	Equipment Under Test
FSB	Front Side Bus
IO	Input Output
IOSF	Integrated On Chip System Fabric / Intel On Chip System Fabric
IP	Intellectual Property
ISA	Industrial Standard Architecture
MMIO	Memory Mapped I/O
NMOS FET	N-type MOSFET
NVRAM	Non-Volatile RAM
OVC	OVM Verification Component
OVM	Open Verification Methodology
PCH	Platform Controller Hub
PCI	Peripheral Component Interconnect
PUF	Physical Unclonable Function
RAM	Random Access Memory
RTL	Register-Transfer Level
SATA	Serial ATA
SoC	System On Chip
TTM	Time To Market
USB	Universal Serial Bus
UUT	Unit Under Test
VLSI	Very Large Scale Integration



## **Model Pengesahan Agnostik untuk Pengujian Sambungan eFUSE**

### **ABSTRAK**

Dalam industri semikonduktor, proses pengesahan adalah penting untuk mencari kesilapan reka bentuk dan membetulkannya sebelum produk dilancarkan. Litar bersepadu semikonduktor biasanya akan diperbaharui dalam kitaran tahunan. Oleh sebab ini, kitaran reka bentuk dan pengesahan yang singkat perlu diutamakan tanpa mengabaikan kualiti produk. Pada masa kini, proses pengesahan litar bersepadu sering menjadi satu faktor yang melambatkan kesediaan produk. Proses pengesahan litar bersepadu perlu diperbaiki supaya ia seiring dengan kemajuan proses reka bentuk litar bersepadu. Dalam kerja ini, penambahbaikan pengesahan sambungan eFUSE (Elektrik FUSE) proses akan difokus. eFUSE merupakan satu ciri yang terdapat dalam litar bersepadu. Ia berfungsi sebagai pusat penyimpanan ‘tetapan’ penting litar bersepadu dan ‘tetapan’ tersebut akan diagihkan ke setiap harta intelek semasa permulaan operasi system komputer. Pengesahan sambungan eFUSE diperlukan untuk memastikan setiap harta intelek mendapat nilai eFUSE yang betul. Dalam kerja ini, konsep model pengesahan sambungan eFUSE agnostik akan diwujudkan dan diuji. Ideanya adalah untuk menghapuskan penjanaan kod ujian secara manual, menambah kecekapan pengujian serta membolehkan penggunaan semula kod ujian dalam projek yang berbeza. Kaedah ini dapat mengurangkan tempoh masa pengesahan sambungan eFUSE secara ketara, iaitu sebanyak 28%. Purata penambahbaikan peratus liputan eFUSE adalah sebanyak 65%. Kesimpulannya, tempoh masa pengesahan sambungan eFUSE dapat dikurangkan tanpa mengorbankan kualiti ujian.

## **Agnostic Validation Test Bench for eFUSE Connectivity Verification**

### **ABSTRACT**

In semiconductor industry, validation is an important process to discover design bugs and have it fixed before the product is released. Semiconductor integrated circuit is normally refreshed in yearly cadence and it is crucial to have a short design and validation cycle, without compromising the product quality. Nowadays, validation process often becomes the bottleneck for product readiness. Integrated circuit validation flow has to be improved in order to keep up with the advancement of integrated circuit design flow. In this work, an improvement method on validation flow is discussed, with particular focus on eFUSE (Electric FUSE) connectivity validation. eFUSE is a feature available in integrated circuit which functions as a central storage for important ‘settings’, and distribute them during system boot up process. eFUSE connectivity validation is needed to ensure each intellectual property is able to retrieve the correct eFUSE value. In this work, the concept of agnostic validation test bench for eFUSE connectivity validation is developed and tested the idea of it is to eliminate manual test development effort, improves validation efficiency and promotes reusability across different projects. By using this methodology, eFUSE connectivity validation time is reduced significantly and recorded an improvement of 28%. There is also an average improvement of 65% in eFUSE coverage percentage. In summary, the eFUSE connectivity validation time frame is shortened, without compromising the test quality.

# **CHAPTER 1**

## **INTRODUCTION**

### **1.1 Overview**

Every semiconductor Central Processing Unit (CPU), chipset or System-on-Chip (SoC) product requires multiple stages of validation or verification work to be done before it is launched to the market. There is a pre-silicon validation which involves testing the chip design using sophisticated simulation and emulation tool to discover functionality bugs. After the chip is fabricated, it will then have to go through post-silicon validation where the chip is being tested using actual use case scenario. Post silicon normally serves as a safety net to discover corner case functionality bugs where pre-silicon failed to catch. In addition to those, there are also electrical validation and performance validation to ensure that the chip is able to meet all the requirements mentioned inside the specification document. All of these validation processes serve only one purpose and that is to materialise as many design flaws as possible before the products reach the customers or end users. There will not be a complete product without going through stages of validation. Hence, this shows that validation plays an important role in semiconductor integrated circuit industry.

In the 21<sup>st</sup> century, innovations in user interface design are causing a revolution in design which drives the semiconductor industry to integrate ever-greater system complexity onto a single chip. The rise in design complexity is motivated by consumer demand for higher performance products as well as increase in integration density which allow more functionalities to be placed on a single chip. Today, a leading edge mobile-enabled electronic system is based on a SoC that contains more than a billion gates, with at least ten interface protocols, hundreds of Intellectual Property (IP) blocks, power domains and clock domains. The register-transfer logic (RTL) could goes up to millions line of codes. This increase in SoC design complexity has created orders of magnitude greater challenges in SoC verification or validation. In addition, there is a strong urge to verify variety of scenarios such as power management, device-level software, analog components, low power structural checks and many more (Lipon, 2014). All this additional feature in advance SoC design indirectly creates more validation tasks. Hence, sheer capacity in verification or validation technology is desperately needed.

Apart from the system complexity, another crucial factor that drives the success of a semiconductor company is the importance of short design time. Consequently, the amount of simulation required to design digital systems also increase significantly. Simulation time typically scales as the square of the increase in system complexity. In order to keep the design time to a minimum and align it to the product launch date, it is critical to structure the simulation environment to make it possible to trade-off simulation performance for model detail in a flexible manner that allows concurrent software and hardware development (Olukotun K. et al., 1998). It is important to have continuous effort to improve the simulation environment so that the validation time is kept at the minimum.

Short design time is important because after the design is conceived and before the system is brought to the market, there is a limited time window in preserving its competitive performance (Olukotun K. et al., 1998).

In summary, design complexity and short design time are the two major challenges that makes the validation work becomes difficult over the years. As design complexity increases, it is almost impossible for designer to design a perfect chip with zero bugs. Hence, the validation work has become extendedly important. Moreover, the short design time factor also pushes the validation task to its limit because it has to meet the product time-to-market (TTM) schedule without sacrificing the quality of validation. Verification is a major obstacle in creating the final product and it is the most important component of timely market release and success (Sethulekshmi R, et al., 2016). For this reason, there is a need to improve the validation methodology to ensure that it is aligned with the design advancement.

## **1.2 Problem Statement**

The integration of more than a million transistors on a single chip has been achieved with the development of semiconductor manufacturing process of 16 nanometer. The complexity of this has made verification the most critical bottleneck in the chip design flow. Approximately 70 to 80 percent of the design cycle is spent on functional verification. The SoC design faces a gap between the production capabilities and time to market pressures. The longer a bug of a design does undetected, the more expensive it will cost when it is discovered. So both innovative verification methodologies and an effective

verification environment are urgently needed (Chai L. et al., 2014). Increase in efficiency of verification, and reduction of time consumed in verification stage are therefore crucial to speed up the entire development process (Li Y. et al., 2009).

SoC verification scope has been increased to verify IPs' integration and on-chip inter-IP communication among multiple IPs (Zhaohui H. et al., 2012). This means, it is an important charter in SoC design team to ensure the connectivity and inter-IP communication is linked or connected correctly. Inside a SoC microprocessor, there will be a dedicated eFUSE controller, which is an IP, to fetch the values or settings from eFUSE memory and distribute them to respective IPs. In order for a SoC to function with desired setting, it is important to make sure that every single IP inside a chip gets the correct values or setting from the eFUSE memory. This is an important technology and eFUSE has a history of wide use in embedded systems (Uhlmann G. et al., 2008). Hence, it is necessary to have eFUSE connectivity validation to check the entire eFUSE distribution flow. This eFUSE connectivity validation validates the data coherency between the source which is the eFUSE memory, and the destination which is the IP. In real world, the eFUSE list could be very huge and it could goes up to hundreds or thousands of values depends on number of IPs inside a chip, or set of functionality that IP designer wish to control using eFUSE. Creating a test manually to validate every single eFUSE connectivity would require huge amount of effort and it is prone to human error.

### **1.3 Aim and Objectives**

The goal of this research is to create an ideal test suit to minimize human effort, where the manual test suit modification or configuration can be reduced to a minimum. Hence, agnostic validation test bench came into the picture where its purpose is to eliminate the test dependency on projects and improve the overall portability of the tests. In addition, the aim is also to create a test bench that is re-usable for future chipsets, which promotes scalability and reusability (Keaveney M. et al., 2008). Efficient reuse can deliver significant savings in design cost and time if implemented correctly (Wakefield A. & Mohd B. J. , 2002). The objectives of this research can be break down into two main subsections:

1. To create a new test suit that is able to minimize human effort, and maximize reusability across projects which fulfil the concept of agnostic validation test bench. By this mean, the aim is to reduce test development effort by introduce automation element into the eFUSE connectivity validation flow and replace the traditional manual test development method.
2. To provide a comparative study between the previous and new eFUSE connectivity validation flow in terms of validation efficiency, simulation time and resource consumed, and eFUSE coverage. Leverage data from the mentioned measurable parameters to analyse if the new eFUSE connectivity validation flow is feasible.

## **1.4 Scope of Work**

In general, the research work will be carried out in different phases to fulfil the two main objectives stated in previous section. Included are the high level scope of work of this research work, which includes what is in scope and will be covered, and also what is out of scope, restrictions or limitations.

1. This research will focus only on eFUSE connectivity validation flow or methodology improvement. This research does not cover functionality validation methodology, latest eFUSE technology or design architecture of eFUSE controller.
2. All work will be carried out in OVM-based simulation environment and will be using System Verilog coding language. Test subject or DUT will be based on the latest available SoC RTL which is in Verilog code.

## **1.5 Thesis Outline**

This thesis consists of 5 main chapters and it is being organized as follows. Chapter one starts with the introduction of the importance of validation work. It provides an overview on the major factors that are driving the needs for validation methodology improvement or breakthrough. This chapter also highlights the problems encountered in a specific validation chapter which is eFUSE connectivity validation. The research objectives and the scope of work have been included in details as well.



Chapter 2 includes the theoretical background and literature review that are related to this research. It contains high level information on the eFUSE design and technology, and validation methodology that is being used in this specific validation chapter, eFUSE connectivity validation. In addition, this chapter also covers the background knowledge of tools and simulation environment that is being used in this research.

Chapter 3 outlines the work flow of this research. This chapter includes the proposed eFUSE connectivity validation methodology which is expected to exhibit more advantages and benefits as compared to the previous methodology. The differences and changes between the new and previous methodology will be included. Details on the new methodology such as the automation script structure and functions will be explained in this chapter as well.

Chapter 4 highlights the results obtained by using the new eFUSE connectivity validation methodology. Comparison is being conducted between the new and previous eFUSE connectivity validation methodology. The results mainly focus on validation efficiency, simulation time and eFUSE coverage percentage between two methodologies. Overview of the Perl script codes is also included in this chapter.

Chapter 5 consists of the conclusion and the recommendation for future work. The major achievement from this research is summarized and highlighted. In addition, it also provides recommendation on how this validation methodology can be reused across other connectivity validation chapter.

## **CHAPTER 2**

### **LITERATURE REVIEW**

In the previous chapter, the importance of pre and post silicon validation of a microprocessor have been discussed. In addition, the brief overview of eFUSE connectivity validation methodology problem is elaborated.

Complementing the previous chapter, this chapter introduces the necessary background concepts and literature relating to pre silicon simulation, semiconductor intellectual property, eFUSE technology, and processor internal interconnects. This chapter starts by reviewing the pre silicon simulation environment, followed by introduction of DUT and semiconductor IP. After that, the background of eFUSE technology is reviewed by looking into eFUSE functionality, application and its evolution. In addition, basic background theory of register access in computer architecture will be discussed. Finally, the internal interconnects between of a processor is reviewed to provide a bigger picture on how IPs communicate with each other, which is crucial for eFUSE distribution and eFUSE verification.

## 2.1 Verification Environment

In pre-silicon validation, there are few popular verification environment that has been widely used in semiconductor industry. One of the famous framework and widely used across semiconductor industry is the Open Verification Methodology (OVM) and this work will be conducted in OVM based simulation, which was developed by Verisity Design in 2001. OVM is a documented methodology with a supporting building-block library for the verification of semiconductor chip designs. OVM test bench composed of reusable verification environments called OVM verification components (OVCs). An OVC is an encapsulated, ready-to-use, configurable verification environment for an interface protocol, a design sub-module, or a full system. Each OVC follows a consistent architecture and consists of a complete set of elements for stimulating, checking, and collecting coverage information for a specific protocol or design (Cadence Design Systems Inc, 2011). Example of OVM framework is shown in Figure 2.1 below. It consists of sequencer, driver, monitor and many other OVC components. OVM environment will allow user to reuse OVM components that is created by other user. User does not need to know what is encapsulated inside and OVM component. User will only need to know the function and the purpose of those component and apply into their test suit. By having this test bench environment, multiple users are able to work on the same test bench and create their own test suit to validate different IP blocks inside a chip. This allows multiple validator to work on a complex chip at the same time. OVM is a complete verification methodology that codifies the best practices for development of verification environments targeted at verifying large gate-count, IP-based SoCs (Malik et al., 2013).

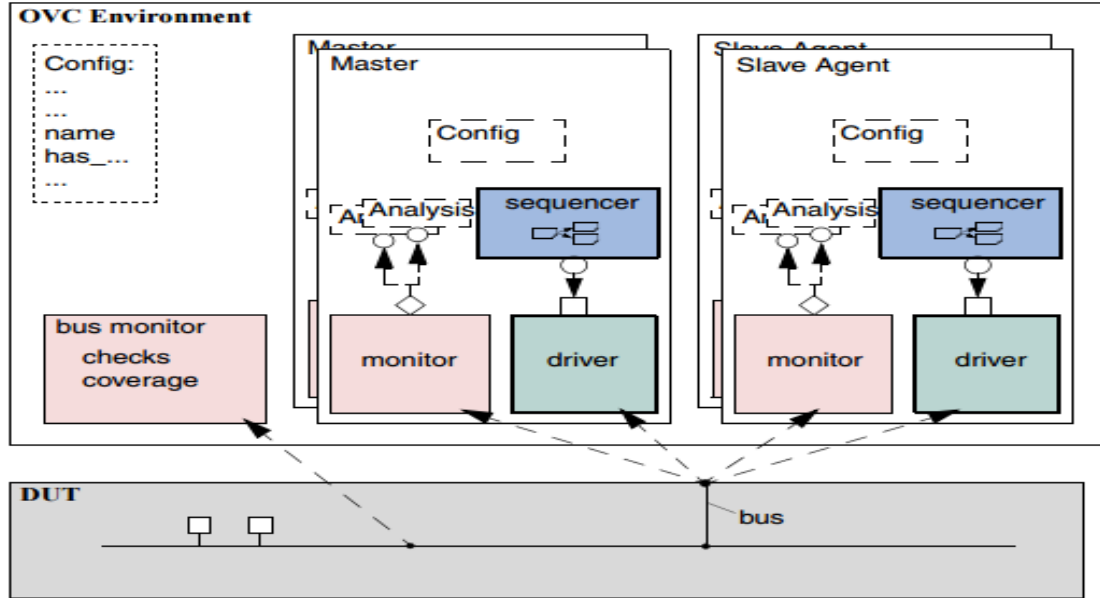


Figure 2.1: OVM verification environment (Cadence Design Systems Inc, 2011)

The test bench environment and test are developed using System Verilog language. SystemVerilog is a special hardware verification language to be used in function verification (Mulani P. D., 2009). It provides high-level data structures available in OO (object-oriented) language, which is similar to C++ programming language. The data structures in OO programming language allows high level abstraction and modeling of complex data types. In addition, System Verilog also provides constructs necessary for modeling hardware concepts or behaviour. For example, clock cycles, tri-state values, wire. All these are similar to the Verilog hardware language which is used for RTL development. With all these advantages, System Verilog is definitely capable and suitable to be used for HDL design simulation.

## **2.2 Device Under Test**

Device/Design under test (DUT), also known as equipment under test (EUT) and unit under test (UUT), is a term used to refer to a manufactured product undergoing testing, either at first manufacture or later during its life cycle as part of ongoing functional testing and calibration checks. In front end verification environment, the chip design (RTL code) will be instantiated as DUT under the test bench. There will be OVC components wrapped around the DUT to form a functional test bench. By referring to chip specification and requirement documents, user will be able create respective tests and inject transactions into the DUT by utilizing OVC components that is generated in the test bench. User can also add in self-check logics or assertion checks inside their test to verify the functionality and behaviour of the DUT.

## **2.3 Semiconductor IP Block:**

Semiconductor IP block is a reusable unit of logic, cell, or chip layout design that is the legally owned and licensed by one party. The intellectual property may be in a form of core, IP core, or IP block that can be licensed to another party and used in their own processor design. Inside a CPU, it normally consists of processing core, graphics core, memory, cache, power management unit and etc. Different types of chip might have different IP blocks depends on the purpose of the chip.

## **2.4 CPU & PCH Architecture**

In today's server architecture, the x86 platform can be considered as one of the dominant architecture used. Majority of the servers in data centers nowadays are based on the x86 architecture. The x86 platform was originally designed for personal computers. However it is now implemented in all types of systems, from netbooks up to the fastest multi CPU servers. This x86 architecture (also known as PC architecture) is based on the original IBM PC and x86 servers first started to appear in the 1990s. During that time, the personal computer were housed in 19 inches racks without dedicated keyboards and monitors (Laan S., 2015).

Over the years, x86 servers became the design environment for adaptive computing technology standard for servers. Their low cost, the fact that there are many manufacturers and their ability to run familiar operating systems like Microsoft Windows and Linux, made them extremely popular. The x86 architecture consists of several building blocks, integrated in a number of specialized chips. These chips are also known as the x86 chipset. The heart of an x86 based system is a CPU from the x86 family. The CPU contains a large number of connection pins to connect address lines, data lines, clock lines, and many more additional logic connections. These are known as Northbridge and Southbridge x86 architecture (Laan S., 2015). The interconnects of this architecture are shown in Figure 2.2.

In the x86 Northbridge and Southbridge architecture, the data path of the CPU, which also known as Front Side Bus (FSB), was connected to a fast Northbridge chip, and function

to transport data between the CPU and, both the RAM memory and the PCIe bus. The Northbridge was also connected to the Southbridge chip by a bus called the Direct Media Interface (DMI). The relatively slow Southbridge chip connected components with slower data paths, like the BIOS, the PCI bus, USB ports, SATA adaptors, and etc (Laan S., 2015).

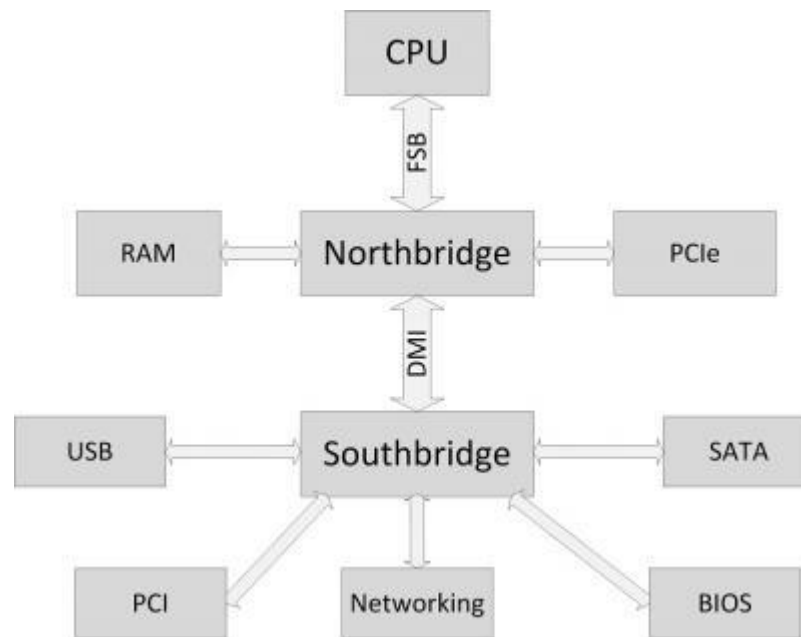


Figure 2.2: CPU, Northbridge and Southbridge connectivity (Laan S., 2015)

In 2008, the Northbridge and Southbridge architecture was replaced by the Platform Controller Hub (PCH) architecture with the introduction of the Intel's 5 Series chipset. The example of interconnect for this architecture is shown in Figure 2.3. In this architecture, the Southbridge functionality is managed by the PCH chip, which is directly connected to the CPU via the DMI (Laan S., 2015). As for the Northbridge, most of its functions were integrated into the CPU while the PCH absorbs the remaining functions in

addition to the traditional roles of the Southbridge. The RAM and PCIe data paths are directly connected to the CPU in this PCH architecture. Today, one of the examples of x86 architectures where the Northbridge is integrated in the CPU is Intel's Sandy Bridge processor (Laan S., 2015).

In 2015, the Skylake architecture is the most recent Intel x86 architecture and some variants of Skylake will have the PCH integrated in the CPU as well, which makes the CPU effectively a full system on a chip (SoC). In 2015, Broadwell-based Xeon D was announced by Intel as its first platform to fully incorporate the PCH in a SoC configuration (Laan S., 2015).

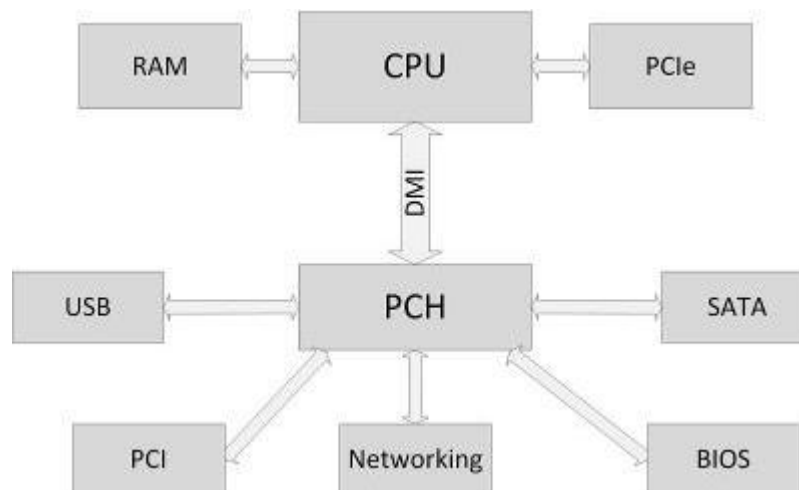


Figure 2.3: CPU and PCH connectivity (Laan S., 2015)



## **2.5 eFUSE Technology**

In a semiconductor chip, there is a technology named as FUSE or eFUSE. eFUSE was originally developed by IBM in 2004. This technology is basically a technique to “hardcode” or “etched” some logics onto a chip. The primary application of this technology is to provide in-chip performance tuning or real time reprogramming (UBM TechInsights, 2010). For example, of the usage is that, if certain sub-systems fail, or are taking too long to respond, or are consuming too much power, the behaviour of the chip can be instantly changed by "blowing" an eFUSE. The reliability of electrical fuses becomes very critical to ensure chip level functionality during its lifetime (Tian C. et al., 2006).

The ability to incorporate a non-volatile memory element on a VLSI chip allows for a host of innovative solutions and applications. However, it is expensive to incorporate charge storage non-volatile memory elements such as Flash or NVRAM into a logic technology. So the alternative was to use eFUSE technology. eFUSE is a resistive link that can be permanently programmed between a conductive state and a highly resistive. The eFUSE state is sensed at chip boot and latched for subsequent uses. eFUSE technology has been used as the key enabler for reconfiguration of the chip function. In addition, it is also functioned as performance programmed using electromigration of the silicide from specification. This technology is widely used in VLSI components (Robson N. et al., 2007).

On the other hand, there were some study to utilize eFUSE in a chip to enhance security protection of a chip. Conventional authentication methods are vulnerable to invasive attacks. Hence, PUF (physical unclonable function) has been introduced to improve the conventional method. Manufacturing flow causes a process variation and this information can be used to identify each chip or integrated circuit. PUF uses CRPs (challenge – response pairs) to generate the secret keys, instead of the conventional method where the secret keys are stored inside IC. eFUSE information are programmed differently on chip to trim the reference voltages. This is dependent on process variations and the value could be different for each chips. Hence, this piece of information can be used to represent a unique characteristic of the ICs and being used in security enhancement as well (Lee & Yang, 2016).

In summary, eFUSE is a hard coded setting of a chip. In order for the chip to function as expected based on the desire eFUSE setting, each IP inside a chip must be able to fetch those eFUSE information into their respective IP block. Figure 2.4 shows an example of how IP blocks are connected to the eFUSE IP. Other than that, there is also other application usage as well such as secure authentication. So, it is crucial that to make sure the value burned into eFUSE rom (non-volatile read only memory) is taken and consumed by the individual IP inside a chip.

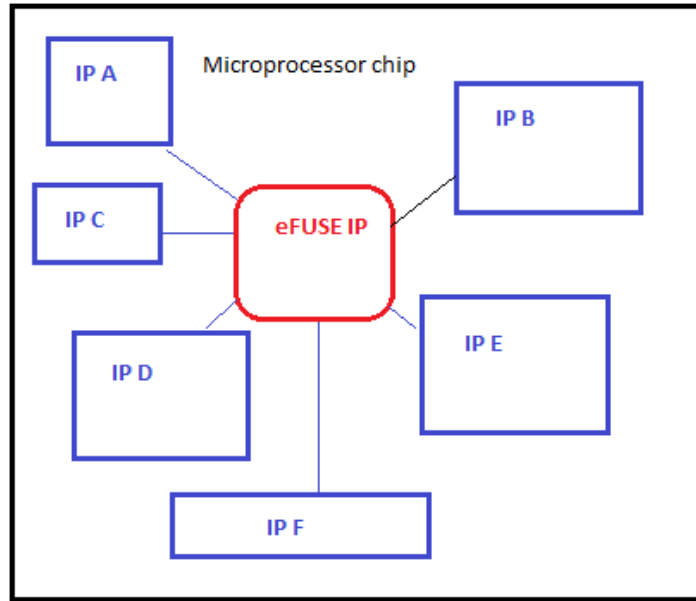


Figure 2.4: eFUSE connection and distribution diagram

### 2.5.1 Evolution from Laser Fuse to Electric Fuse (Robson N. et al., 2007)

Circuit elements are not perfect. In order to improve yield and circuit robustness, circuit spares are designed, tested and available for replacement and fuses play an important role to enable the replacement. For example, fuses enable circuit trimming for process variances which is needed to optimize performance. Another example is using fuse to encode the electronic chip ID which is useful throughout a products life cycle. This electronic chip ID also called chip's DNA. On the customization point of view, fuses can be used to personalize and deliver the correct customization for some products that required unique configuration to serve different customer needs (Tonti W., 2008).

For several decades, laser fuse was the only choice for all the mentioned applications. The laser fuse employs a top level metal layer, which is intact or blown to store the non-volatile

data on integrated circuits. This non-volatile feature allows keeping the data bits permanently. Initially, laser fuse is widely used for electrical chip identification (ECID) and for redundancy in high density and low cost standalone memories. However, there are few downsides for laser fuse. First is the logistics of the data infrastructure where the test system that generates the fuse blow string and the laser fuser are different platforms. Secondly, it is lack of scalability whereby the fuse dimension is related to the CO<sub>2</sub> laser wavelength used for fusing. In addition, this is one time wafer only programming because the fuse has to be at the top most metal layer. The third is the laser fuse occupies up to 5% of die area which is large amount of physical size.

Modern VLSI systems require reconfiguration of functional features in the field which cannot be realized by the traditional laser fuse. The electrical fuse (eFUSE) offers a small, scalable solution that can be contained within one level of metal wiring with no higher level metal wiring restrictions. This allows enabling larger data bit storage on chip. Another advantage is that the energy for programming the fuse is transmitted electrically instead of optically. This allows a more precise delivery to the selected fuse without affecting its neighbour components. Other than this, fuse programming can be done at different stage such as wafer final test, through module test or system board test. These eFUSE features not only replace the laser fuse applications and features including field repairable memory, field programmable memory, and ID & security chips programmable in the field with RF technology, it also allows a self-reconfiguring system-on-chip with build-in self-test.

In the history of development of eFUSE using silicided polysilicon, one requirement since the beginning is that the fuse link requires no additional wafer processing. In addition, the fuse device needs to be robust across the technology window. In early process development fuse operation can be adjusted with external voltage stimulus. As the technology matures, the optimized design of the fuse circuits is converged based on application needs. Early work on eFUSE focused on thermally rupturing metal fuses but this material produced significant collateral damage. Later on in subsequent work, silicided polysilicon showed promising results and the first generation of electrical fuse was implemented using tungsten silicide polysilicon process. At this stage, eFUSE is used specifically for DRAM repair. At that time, metal laser fuse was still the preferred method of manufacture and eFUSE basically mimicked the operation of laser fuse, with high resistance achieved by breaking the fuse link. There were reliability concerns with this early non-electro migration fuse work. Because of this reason, metal laser fuse remained the dominant or preferred choice for this and the next logic technology node.

The second generation of electrical fuse development began with the 0.18um logic technology using cobalt silicided polysilicon and the basic building block of the fuse remained the same. The fuse structure was optimized to improve the programming window. This fuse link introduced programming via electro migration, with no collateral damage resulting in a wide window of operation. To produce the desired electro migration phenomena, a programming current of 12mA and anode voltage of 5V range were established. The fuse achieved typical programmed resistance in excess of 100K ohm with all fuses over 10K ohm. The fuse link requirements drive the initial circuit designs for the

programming FET and sense circuits. This fuse programming and sensing scheme was migrated to the next technology nodes. There were minimal changes during the migration.

Due to the high programming and sense current requirements, special consideration is required during design integration of the fuse elements. Legacy designs with excessive wiring resistance to the fuse circuits exhibited local programming voltage supply pin ( $V_{\text{FSOURCE}}$ ), drain voltage supply pin ( $V_{\text{DD}}$ ), and ground (GND) variation. This resulted in inadequate fuse programming condition as well as reduced sense signal margin during sense operation. It is important to reduce the resistance of  $V_{\text{FSOURCE}}$  and GND nets. As a solution for this, distributed or lumped NMOS clamp FETs were added or fitted to the  $V_{\text{FSOURCE}}$  lines and a time staggered sensing scheme was devised. This approach allowed the GND for the sense amplifier to be tightly coupled to the grounded  $V_{\text{FSOURCE}}$ . By having this, fuse sensing margin can be improved without degrading the fuse programming margin.

The electrical fuse solution ( $I_{\text{PROG}} = 10\text{mA}$  and  $V_{\text{FSOURCE}} = 3.5\text{V}$ ) was adopted in manufacturing for select products at the 130nm node. At this time, the design community was eager to adopt the eFUSE technology across mainstream designs and a single bit kit was offered for foundry customer solutions. The kit comprised a fuse link, a programming NMOS FET, and a single ended sense design with a  $V_{\text{FSOURCE}}$  clamp FET for the 90nm generation. ASIC library IP block included this kit as part of its library and it is widely used for embedded dynamic random access memory (eDRAM) redundancy. The eFUSE kit was employed by the eDRAM system with a self-repair eFUSE controller circuit and

built-in-self test (BIST). Since then, eDRAM macros were able to be tested, repaired and retested in a single touch down on the automated test equipment (ATE).

Variety of specific voltages were used by eDRAM on integrated circuit or chip. These include the bitline high voltage, the negative wordline low voltage, the wordline boost voltage and the body bias on the pass transistor. Charge pumps are used to generate all these voltages on chip which are in turn, set using digital to analog converters (DACs). It is possible to use the BIST to set these voltages using eFUSE in 90nm eDRAM technology. This can be done on a die-by-die basis during test to maximize wafer yield. This is a good example of how on-chip programming coupled with BIST has led to autonomic capability. Due to the benefits over laser fuse became apparent to the product design, manufacturing and test communities, the use of eFUSE has spread across different technology variants. One of the example is that eFUSE solutions were used in IBM's 90nm bulk and silicon on insulator (SOI) technology products, which includes game console chips and mainframe chipsets such as the POWER5 microprocessors.

There were additional challenges when scaling into 65nm technology node. Due to polysilicon process change to nickel silicide, this resulted in a change for the fuse element post programmed resistance distribution. As a solution to this new challenge, differential sensing was introduced to offer a robust solution. Several differential sense schemes were evaluated in order to find the best sensing circuitry.

In the fourth generation of electrical fuse development, low-voltage ( $I_{\text{PROG}} = 7\text{mA}$  and  $V_{\text{FSOURCE}} = 1.5\text{V}$ ) fuse in 65nm and 45nm logic technology were first adopted as starting

point. To accommodate a lower fuse programming voltage requirement with standard gate oxide FETs, the Nickel Silicide fuse element was scaled. The density was also improved with the One-Time Programmable Read-Only-Memory (OTPROM) architecture. Two different macros were developed to support a variety of customers' requirements. First macro was the general purpose one dimensional linear array offering for bulk foundry customers who require minimal design migration to the next technology node. Second macros was the high density two dimensional array OTPROM 4Kb building block IP offering that can be tiled to create larger arrays.

eFUSE scales with technology but Laser Fuse does not. eFUSE relies on the front end process technology, but laser fuse relies on the back end process technology. Hence, eFUSE can be designed to not impact the back end. In short, eFUSE consists of the following advantages. Firstly, it can be enabled at any level of assembly and function within the product. Secondly, it does not require any external programming stimulus at low level (e.g wafer) of processing. eFUSE also exhibits autonomic capability which is not found in Laser Fuse. As for overall performance, eFUSE is able to make reliable product “more reliable” (Tonti W., 2008).

## **2.6 Register Space**

The CPU and the PCI devices need to access memory that is shared between them. Device drivers uses memory to control the PCI devices and to transfer information between them. Registers normally consist of a small amount of storage. Typically, the shared memory contains control and status registers for the PCI devices. These registers are used to control



the PCI devices and also provides status update to the CPU or host. Some registers have specific hardware functions such as for power management and performance control. Others may just store information and may be read-only or write-only. The CPU's system memory could be used for this shared memory as well. But there is a drawback for this, where the CPU would have to stall when PCI devices access the memory. CPU can only resume its task after the PCI device completed its memory access because access to memory is generally limited to one system component at a time. As a result, the entire system could be slow down significantly. In addition, it is also not recommended to allow the system's peripheral devices to access main memory in an uncontrolled way. If there is a rogue device accesses some core section of the main memory, this could make the system very unstable and compromised. Accesses by peripheral devices into the system's memory is very strictly controlled using DMA (Direct Memory Access) channels and peripheral devices have their own dedicated memory spaces to do its task. ISA (Industrial Standard Architecture) devices have access to two address spaces, which are ISA I/O (Input/Output) and ISA memory. On the other hand, PCI devices have access to three address spaces. They are known as PCI I/O, PCI Memory and PCI Configuration space. All of these address spaces are accessible by the CPU. For example, device drivers will be using the PCI I/O and PCI Memory address spaces. PCI initialization code uses PCI Configuration space within the Linux kernel (Rusling, 1999).

### **2.6.1 PCI Configuration Space**

PCI devices have a set of registers which is known as 'Configuration Space'. On top of this register space, The PCI Configuration Space format is shown in Figure 2.5. PCI

Express introduces Extended Configuration Space for devices. Configuration space, including the extended configuration space, registers are mapped to memory locations. Configuration space registers are accessed by the device drivers and diagnostic software. Operation systems such as Windows and Linux will have dedicated APIs to allow access to the device configuration space. However there are cases where operating system does not have access methods defined or APIs for memory mapped configuration space requests. Under such condition, the device drivers or diagnostic software has to access the configuration space in a compatible manner which does not violate the operating system underlying access rules. In all systems, device drivers are encouraged to use APIs provided by the operating system for configuration space registers access. PCI Express defines an Enhanced Configuration Access mechanism (ECAM) for systems that do not implement a processor architecture specific firmware interface standard that allows configuration space registers access (Advanced Micro Devices Inc, 2008).